



00-02

1756

Agent Docket No.: Stanford MxL 01

#5

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Application of)
)
Charles D. SCHAPER)
)
Application No: 09 / 898,521)
)
Filed : July 3, 2001)
)
Title: **Molecular Transfer lithography**)
)
-----)

Palo Alto, California 94306
June 6, 2002

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR § 1.97

Assistant Commissioner for Patents
U.S. Patent and Trademark Office
Washington, DC 20231

TO THE COMMISSIONER FOR PATENTS:

In accordance with the duty of disclosure under 37 CFR § 1.56 and in accordance with 37 CFR § 1.97 and 37 CFR § 1.98, enclosed is an Information Disclosure Statement PTO-1449B substitute, together with photocopies of the ten articles cited on that form.

It is requested that the cited documents be considered by the Examiner in the examination of the above cited patent application, and that the enclosed copy of the Information Disclosure Statement Form PTO-1449 be initialed by the Examiner to indicate such consideration, and that a copy of this initialed form be returned to the applicants.

Pursuant to 37 CFR § 1.97, the submission of this Information Disclosure Statement is not to be construed as a representation that a search has been made, and is not to be construed as an admission that the information cited within is material to patentability.

RECEIVED
JUN 18 2002
TC 1700

Please address all further correspondence to

Franklin Schellenberg
4023 Villa Vista
Palo Alto, CA 94306

Respectfully submitted,



Franklin Schellenberg
Registration No. 47,315
Day: 408-487-7082
Eve: 650-856-3975

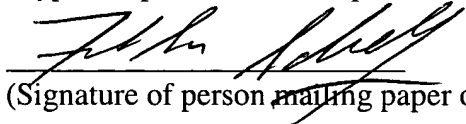
CERTIFICATE OF MAILING

Date of Deposit June 6, 2002

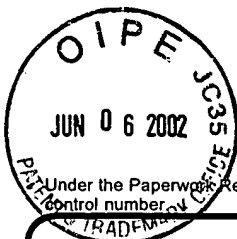
I hereby certify that this paper or fee is being deposited within the United States Postal Service "Express Mail Post Office to Addressee" service under 37 C.F.R. § 1.10 on the date indicated above and is addressed to the Assistant Commissioner for Patents, Box Patent Application, Washington DC 20231.

Franklin Schellenberg

(Typed or printed name of person mailing paper or fee)



(Signature of person mailing paper or fee)



Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

| | | | | | |
|---|---|-----------------------------|--------------------|-------------------------------|--------------|
| Substitute for form 1449B/PTO | | Complete if Known | | | |
| | | Application Number | 09 / 898,521 | | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary) | | Filing Date | July 3, 2001 | | |
| | | First Named Inventor | Charles D. SCHAPER | | |
| | | Group Art Unit | | | |
| | | Examiner Name | | | |
| Sheet | 1 | of | 1 | Attorney Docket Number | STAN MXL 001 |

| OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS | | | |
|--|-----------------------|--|----------------|
| Examiner Initials ¹ | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ² |
| | | Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Imprint Lithography with 25-Nanometer Resolution", Science Vol. 272, April 5, 1996 pp. 85-87, USA. | |
| | | Stephen CHOU, Peter KRAUSS, & Preston RENSTROM. "Nanoimprint Lithography", Journal of Vacuum Science & Technology B Vol. 14(6), Nov/Dec. 1996 pp. 4129-4133, USA. | |
| | | Babak HEIDARI, Ivan MAXIMOV, Eva-Lena SARWE, & Lars MONTELIUS, "Large scale nanolithography using nanoimprint lithography", Journal of Vacuum Science & Technology B Vol. 17(6), Nov/Dec. 1999 pp. 2962-2964, USA. | |
| | | Jan HAISMA, Martin VERHEIJEN, Kees VAN DEN HEUVEL, & Jan VAN DEN BERG, "Mold-assisted nanolithography: A process for reliable pattern replication", Journal of Vacuum Science & Technology B Vol. 14(6), Nov/Dec. 1996 pp. 4124-4128, USA. | |
| | | Thomas WHIDDEN, David FERRY, Michael KOZICKI, Enoch KIM, Amit KUMAR, James WILBUR, & George WHITESIDES, "Pattern transfer to silicon by microcontact and RIE", in Nanotechnology Vol. 7, 1996, pp. 447-451, UK. | |
| | | James WILBUR, Amit KUMAR, Hans BIEBUYCK, Enoch KIM, & George WHITESIDES, "Microcontact printing of self-assembled monolayers: applications in microfabrication", in Nanotechnology Vol. 7, 1996, pp. 452-457, UK. | |
| | | Younan XIA & George WHITESIDES, "Soft lithography", in Annual Reviews of Material Science Vol. 28, 1998, pp. 153-184, USA. | |
| | | Shinichi UEKI, Isao ASHIDA, & Hiroichi KAWAHIRA, "New data processing of dummy pattern generation adaptive for CMP process", in Photomask and X-Ray mask Technology VI, H. Morimoto, ed. Proceedings of the SPIE Vol. 3748, April 1999 pp. 265-272, USA. | |
| | | M. COLBURN, S. JOHNSON, M. STEWART, S. DAMLE, T. TAILEY, B. CHOI, M. WEDLAKE, T. MICHAELSON, S.V. SREENIVASAN, J. EKERDT, & C. Grant WILLSON, "Step and flash imprint lithography: A new approach to high-resolution printing", in Emerging Lithographic Technologies III, Y. Vladimirovsky, ed. Proceedings of the SPIE Vol. 3676, March 1999 pp. 279-389, USA. | |
| | | P. RUCHHOEFT, M. COLBURN, B. CHOI, H. NOUNU, S. JOHNSON, T. BAILEY, S. DAMLE, M. STEWART, J. EKERDT, S.V. SREENIVASAN, J.C. WOLFE, & C. Grant WILLSON, "Patterning curved surfaces: Template generation by ion beam proximity lithography and relief transfer by step and flash imprint lithography", Journal of Vacuum Science & Technology B Vol. 17(6), Nov/Dec. 1996 pp. 2965-2969, USA. | |

| | | | |
|---------------------------|--|------------------------|--|
| Examiner Signature | | Date Considered | |
|---------------------------|--|------------------------|--|

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Applicant's unique citation designation number (optional). ² Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

RECEIVED
JUN 18 2002
TC 1700